Press Release

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Nanonex
Engine for Nanotechnology ™

Nanonex Delivers Advanced Nanoimprint Tool to Northeastern University

Princeton NJ, June 28, 2007: Nanonex Corporation, the inventor and world's leading provider in nanoimprint lithography solutions with the longest history, announces the delivery of a Nanonex NX-2000 system to the George J. Kostas Nanoscale Technology and Manufacturing Research Center at Northeastern University, in Boston, MA.

The Nanonex NX-2000 is a full-wafer nanoimprinter capable of all forms of imprint: thermal, photo-curable, embossing and their combinations, with sub-5 nm resolution. Based on Nanonex's unique patented Air Cushion Press™ and other technologies, the NX-2000 offers unsurpassed nanoimprint uniformity, flexibility in handing different sizes and types of wafers and masks, high yield and easy operation.

The NX-2000 was purchased for the Center for High-rate Nanomanufacturing by Prof. Ahmed Busnaina, director of the NSF's Center for High-rate Nanomanufacturing (CHN), focusing on Fabrication of Nanotemplates and Synthesis of Nanotubes. Nanonex is proud to support the leading edge research of the CHN.

About Nanonex Corporation
Nanonex is the inventor of "nanoimprint lithography", the world's first nanoimprint lithography company, and the world's leading provider of nanoimprint solutions that include equipment, masks, resists and processes. Nanonex's patented and proprietary nanoimprint lithography (NIL) solutions and Air-Cushion Press™ can manufacture 3D nanostructures with sub-5 nm resolution, large-area uniformity, accurate overlay alignment, high throughput, and low cost. Nanonex NIL solutions have been adopted by a broad spectrum of industry applications, such as optical devices, data storage, displays, light emitting diodes, semiconductor ICs, biotech, chemical synthesis, and advanced materials. Nanonex has over 100 customers and an installed base of more than 40 tools world-wide. Visit www.nanonex.com for additional information.

The Center for High-rate Nanomanufacturing is focused on developing tools and processes that will enable high-rate/high-volume bottom-up, precise, parallel assembly of nanoelements (such as carbon nanotubes, nanoparticles, etc.) and polymer nanostructures. The center nanotemplates are utilized to conduct fast massive directed assembly of nanoscale elements by controlling the forces required to assemble, detach, and transfer nanoelements at high rates and over large areas. The developed

nanotemplates and tools will accelerate the creation of highly anticipated commercial products and will enable the creation of an entirely new generation of applications.